Sor 10/712,460

## Refine Search

## Search Results -

Terms	Documents
(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay same wafer	14

Database:	US Pre-Grant Publication Full-Text Database US Patents Full-Text Database US OCR Full-Text Database EPO Abstracts Database JPO Abstracts Database Derwent World Patents Index IBM Technical Disclosure Bulletins		
Search:	L3		Refine Search
	Recall Text Clear		Interrupt
	Search History	***************************************	

## DATE: Sunday, March 20, 2005 Printable Copy Create Case

<u>Set</u> Name side by side	Query	Hit Count	Set Name result set
DB=	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ		
<u>L3</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay same wafer	14	<u>L3</u>
<u>L2</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same (delay near1 time)	22	<u>L2</u>
<u>L1</u>	(rtp or (rapid adj thermal) or nitridation or oxidation) same (clean or cleaning or ((native adj oxide) near3 (etch\$3 or remov\$3))) same delay	144	<u>L1</u>

**END OF SEARCH HISTORY**